

ABSTRACT

SUBSTRATE WITH ELECTRICALLY CONDUCTIVE FILM, SUBSTRATE WITH
MULTILAYER REFLECTIVE FILM, REFLECTIVE MASK BLANK, REFLECTIVE MASK,
5 AND METHOD OF MANUFACTURING SEMICONDUCTOR DEVICE

A substrate that is provided with an electroconductive film is obtained, the substrate
being for manufacturing a reflective mask, with which positional offset of the reflective mask
during pattern transfer can be prevented. The substrate provided with an electroconductive film
10 has an electroconductive film formed on one surface on the main surface of a substrate for a
mask blank used for lithography, wherein the substrate provided with an electroconductive film
is characterized in that the coefficient of static friction of the electroconductive film surface is
0.25 or above.

15
FIG. 5